

Film deposition and heat treatment equipment line-up

We perform various film deposition and heat treatment according to customer's request. The carbon deposition can be carried out by PBII for SiC pre-annealing treatment, the annealing treatment can be done with RTA. We can perform a series of treatments before and after annealing. In addition, we accept requests for semiconductor pre-processing.

Deposition

PBII (Plasma Based Ion Implantation)
Can carry out carbon deposition



Heat treatment

RTA (Rapid Thermal Annealing) (vertical)
High frequency induction heating
Heat treatment up to 1800 °C possible



Oxidation furnace (Horizontal)
Oxidation, heat treatment
Heat treatment up to 1000 °C possible

